

# Lecture 4

## Microelectronic Devices

*pn* junctions and diodes : lectures 4-5

- pn junction under bias
- Depletion capacitance
- reverse-biased pn-junction
- pn-junction: breakdown mechanisms

## Comments for the exercise: Series2/ex4

We consider a p-type silicon sample doped with boron at a concentration of  $N_A = 10^{16} [cm^{-3}]$ . The energy difference between the valence level  $E_v$  and the acceptor ionization level  $E_A$  is  $E_a = 45 [meV]$ . The impurity level degeneracy factor is  $\beta_a = 4$  in this case.

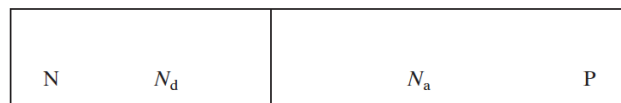
Find the temperature where 90% of dopants are ionized

- Typically in this situation  $\frac{N_A - N_A^-}{N_A}$ , approximated with  $\beta_a N_A \cdot e^{-\frac{E_f - E_A}{kT}}$
- difficulty -  $E_F$  is unknown!
- typically we determine from the hole concentration  $E_F - E_v = kT \cdot \ln(N_v/p)$
- difficulty -  $T$  is unknown!
- Solution: cancel out the Fermi level:  $p_0 + N_A - N_A^- \approx N_A \rightarrow \frac{N_A - N_A^-}{p_0 + N_A - N_A^-} = 0.1$

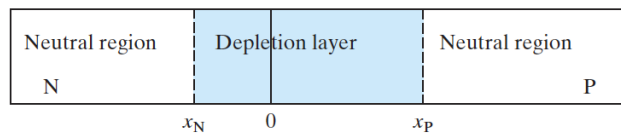
$$\frac{\beta_a N_A \cdot e^{-\frac{E_f - E_A}{kT}}}{N_v(T) \cdot e^{-\frac{E_f - E_v}{kT}} + \beta_a N_A \cdot e^{-\frac{E_f - E_A}{kT}}} \rightarrow \frac{N_A - N_A^-}{p_0 + N_A - N_A^-} = \frac{1}{\frac{N_v(T)}{\beta_a N_A} \cdot e^{-\frac{E_A - E_v}{kT}} + 1} = 0.1$$

Can be solved!

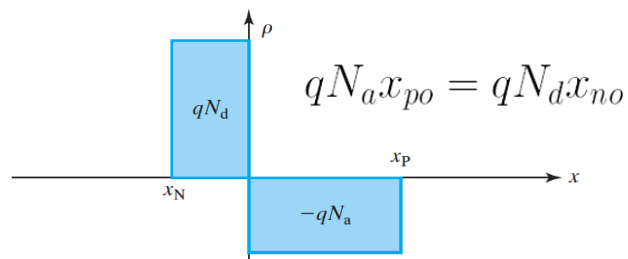
# pn junction: depletion regions, built-in field and potential profile



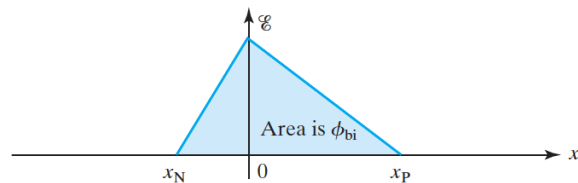
(a)



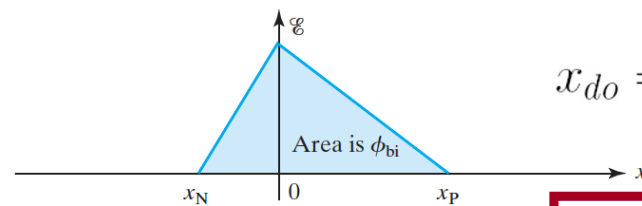
(b)



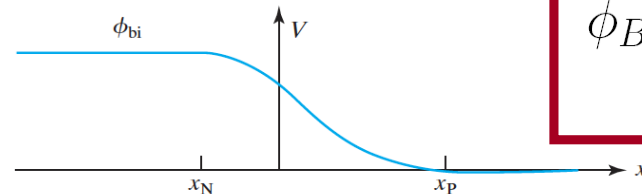
(c)



(d)



(e)



(f)

$$x_{do} = x_{no} + x_{po} = \sqrt{\frac{2\epsilon_s \phi_B (N_a + N_d)}{q N_a N_d}}$$

$$\phi_B = \phi_n - \phi_p = \frac{kT}{q} \ln \frac{N_a N_d}{n_i^2}$$

## pn junction (with no applied bias): numerical example

*A  $p^+n$  junction has  $N_A = 10^{20} \text{ cm}^{-3}$  and  $N_D = 10^{17} \text{ cm}^{-3}$ . What is a) its built in potential, b)  $W$ , c)  $x_n$ , and d)  $x_p$ ?*

$$\phi_{\text{bi}} = \frac{kT}{q} \ln \frac{N_d N_a}{n_i^2} \approx 0.026 \text{ V} \ln \frac{10^{20} \times 10^{17} \text{ cm}^{-6}}{10^{20} \text{ cm}^{-6}} \approx 1 \text{ V}$$

$$W_{\text{dep}} \approx \sqrt{\frac{2\epsilon_s \phi_{\text{bi}}}{q N_d}} = \left( \frac{2 \times 12 \times 8.85 \times 10^{-14} \times 1}{1.6 \times 10^{-19} \times 10^{17}} \right)^{1/2}$$
$$= 1.2 \times 10^{-5} \text{ cm} = 0.12 \text{ } \mu\text{m} = 120 \text{ nm} = 1200 \text{ } \text{\AA}$$

$$|x_p| = |x_n| N_d / N_a = 0.12 \text{ } \mu\text{m} \times 10^{17} \text{ cm}^{-3} / 10^{20} \text{ cm}^{-3} = 1.2 \times 10^{-4} \text{ } \mu\text{m}$$
$$= 1.2 \text{ } \text{\AA} \approx 0$$

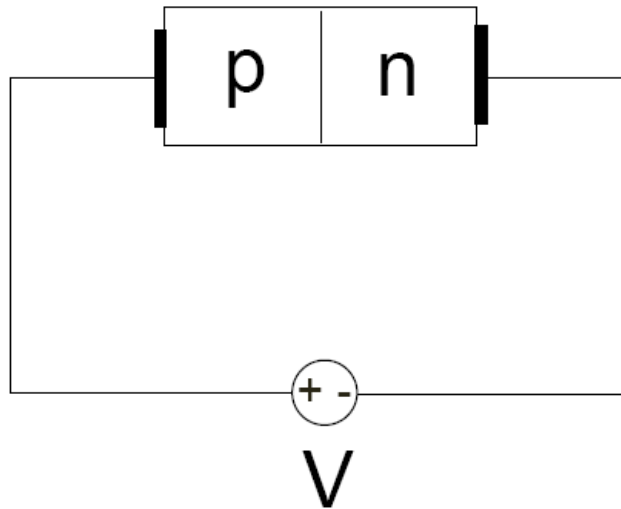
*It is useful to remember that  $W_{\text{dep}} \approx 0.1 \text{ } \mu\text{m}$  for  $N = 10^{17} \text{ cm}^{-3}$*

## What happens if voltage is applied to a pn junction?

- electrostatics of a pn junction if a voltage is applied across its terminals
- Why does a pn junction behave in some way like a capacitor?

## Introduction to pn junction

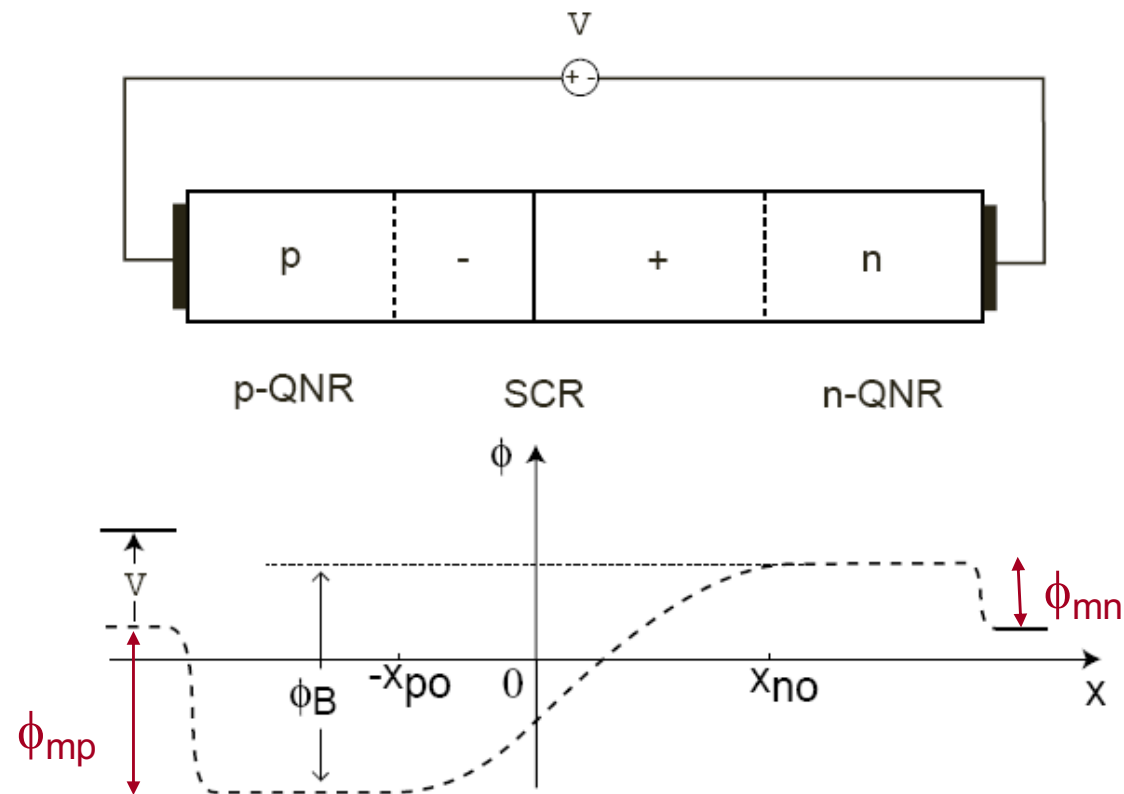
Convention for pn junction bias:



- $V > 0$  called **forward bias** (polarisation directe)
- $V < 0$  called **reverse bias** (polarisation inverse)

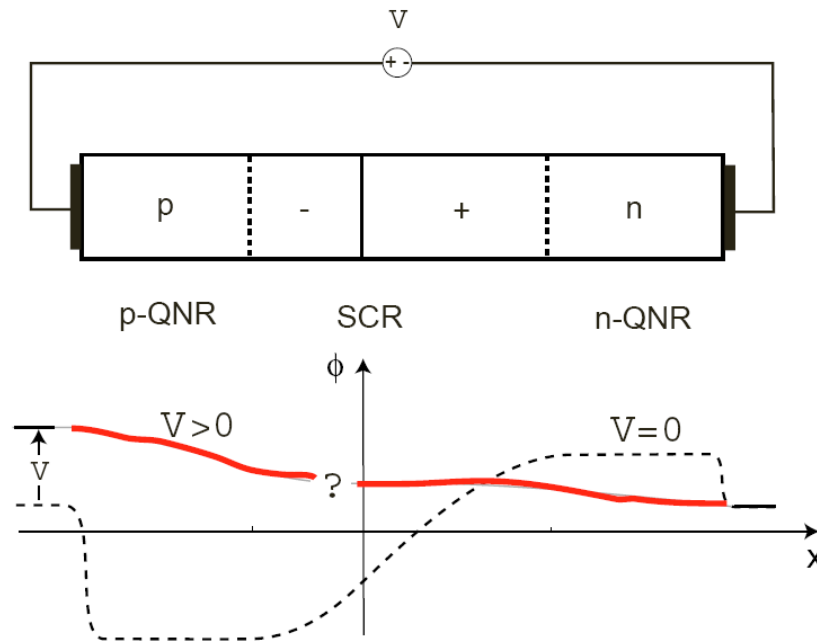
## pn junction: forward bias (1)

Positive voltage applied to p-side with respect to n-side:  
what's the effect of applying a  $V$  forward bias?



## pn junction: forward bias (2)

How does potential distribution inside junction change as a result of bias? Where  $V$  drops the most?



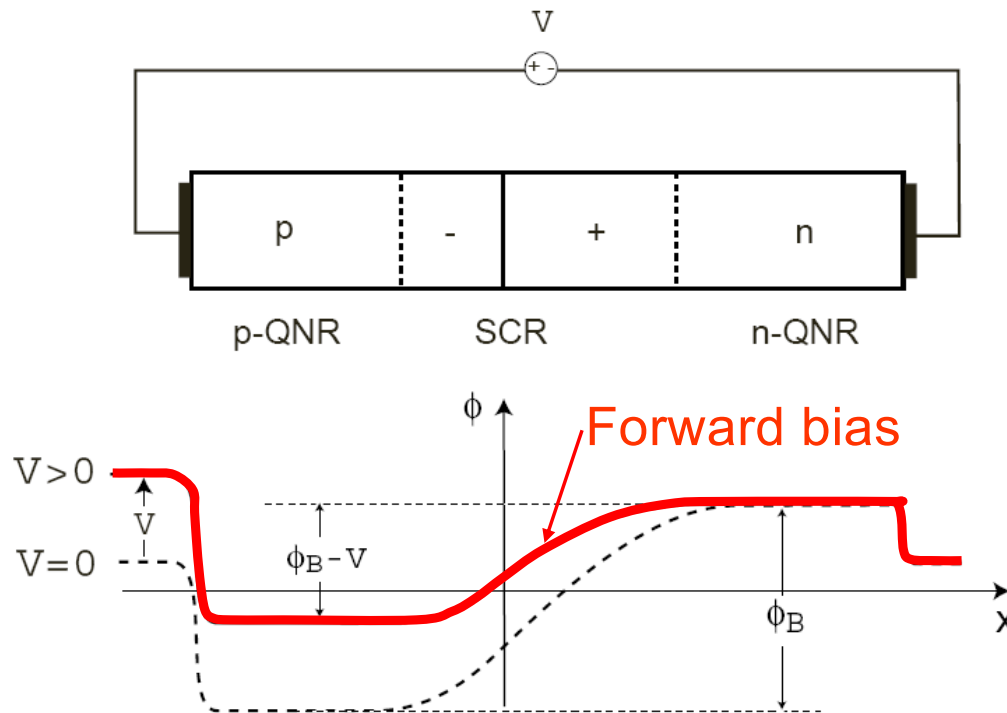
How  $V$  is distributed across:

- metal/p-QNR contact?
- p-QNR?
- SCR?
- n-QNR?
- metal/n-QNR contact?



## pn junction: forward bias (3)

Answer: essentially all the voltage drops across the space charge region (SCR)



The potential across the junction

(**potential barrier**) is:

- in equilibrium (no bias) :

$$\phi_B$$

- @ forward bias:

$$\phi_B - V < \phi_B \quad V > 0$$

- @ reverse bias:

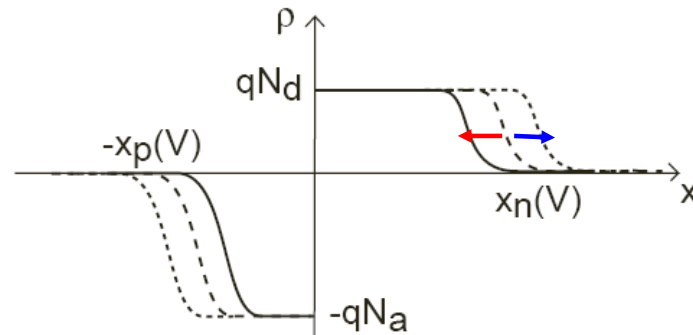
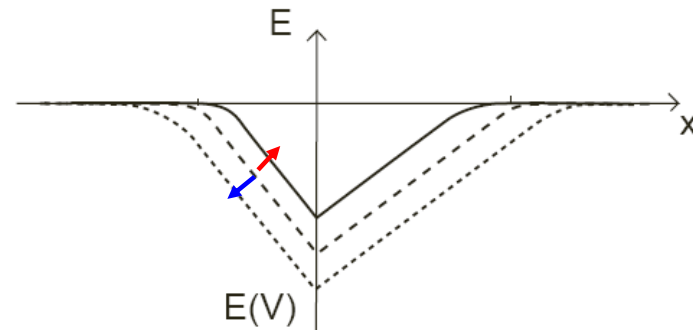
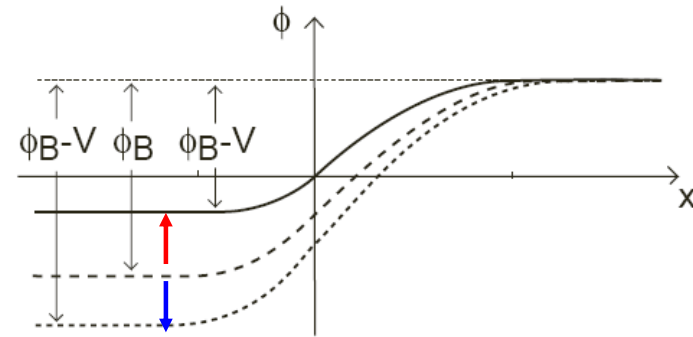
$$\phi_B - V > \phi_B \quad V < 0$$

## SCR electrostatics (1)

Forward bias  $V > 0$   
 0-bias  $V = 0$   
 Reverse bias  $V < 0$

### Main effects

- **forward bias:**
  - Built-in potential decreases*
  - Electrical field decreases*
  - Depletion width decreases*
- **reverse bias:**
  - Built-in potential increases*
  - Electrical field increases*
  - Depletion width increases*



## SCR electrostatics (2)

Analytical formulation of electrostatics of SCR identical to that of thermal equilibrium with:

$$\phi_B \longrightarrow \phi_B - V$$

$$x_n(V) = \sqrt{\frac{2\epsilon_s(\phi_B - V)N_a}{q(N_a + N_d)N_d}} \quad x_p(V) = \sqrt{\frac{2\epsilon_s(\phi_B - V)N_d}{q(N_a + N_d)N_a}}$$

Other results that  
can be derived:

$$x_d(V) = \sqrt{\frac{2\epsilon_s(\phi_B - V)(N_a + N_d)}{qN_aN_d}}$$

$$|E|(V) = \sqrt{\frac{2q(\phi_B - V)N_aN_d}{\epsilon_s(N_a + N_d)}}$$

## SCR electrostatics (2) simplified formulas

$$x_d(V) = \sqrt{\frac{2\epsilon_s(\phi_B - V)(N_a + N_d)}{qN_aN_d}}$$

$$|E|(V) = \sqrt{\frac{2q(\phi_B - V)N_aN_d}{\epsilon_s(N_a + N_d)}}$$

$$x_n(V) = x_{no} \sqrt{1 - \frac{V}{\phi_B}}$$

$$x_p(V) = x_{po} \sqrt{1 - \frac{V}{\phi_B}}$$

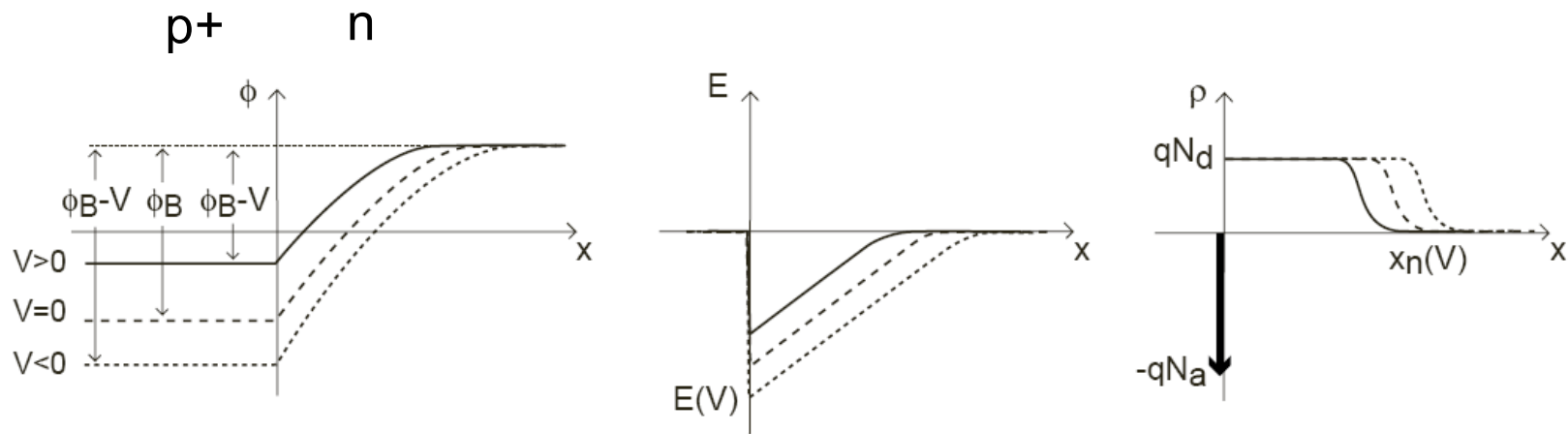
Rules of square root:

$$x_d(V) = x_{do} \sqrt{1 - \frac{V}{\phi_B}}$$

$$|E|(V) = |E_o| \sqrt{1 - \frac{V}{\phi_B}}$$

## Case of strongly asymmetric junctions: p+n

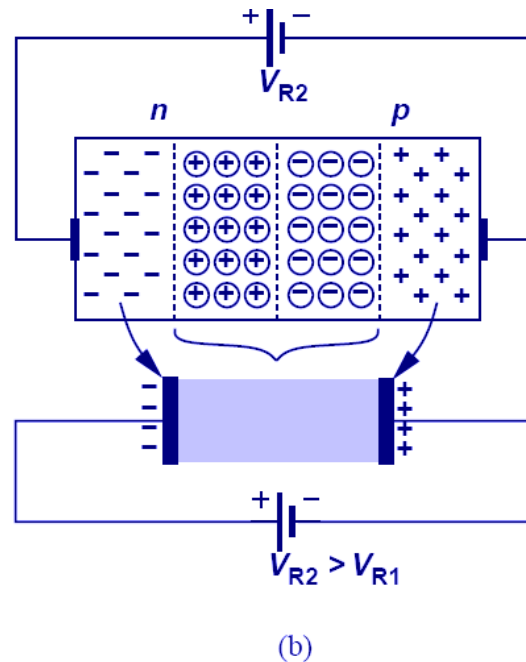
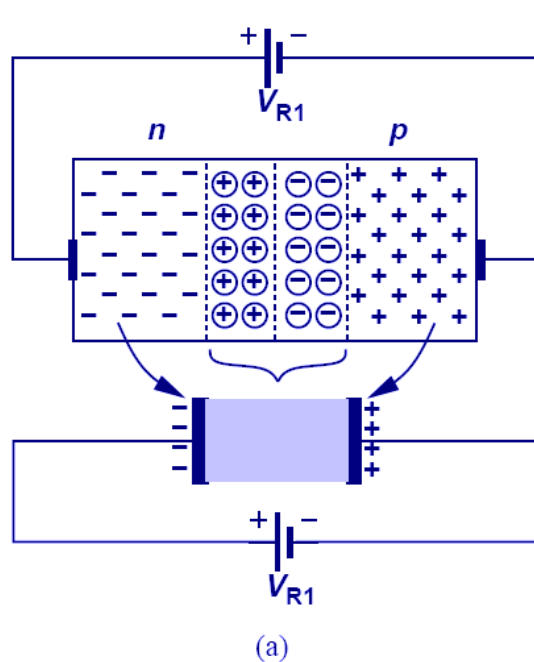
All changes take place in lowly doped side!



$$x_n(V) = x_{no} \sqrt{1 - \frac{V}{\phi_B}}$$

# PN Junction Small-Signal Capacitance

- A reverse-biased PN junction can be viewed as a capacitor, for incremental changes in applied voltage.



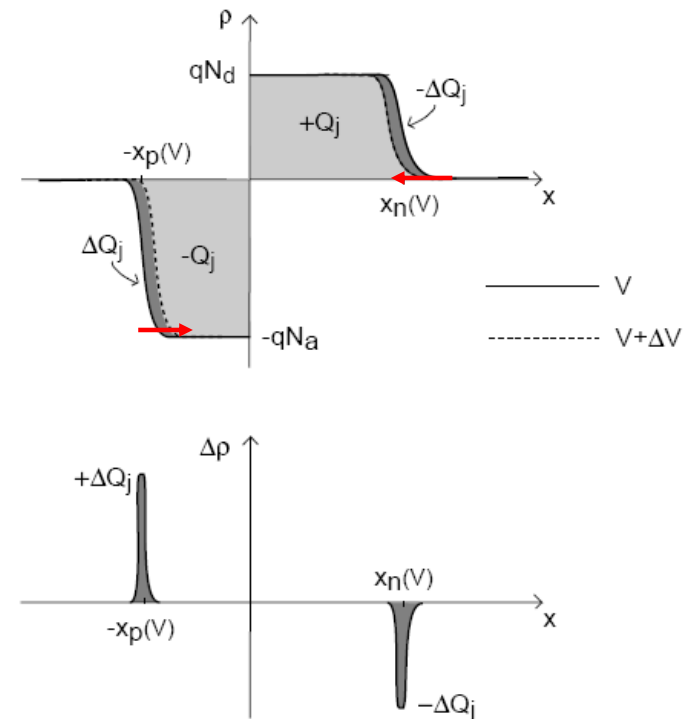
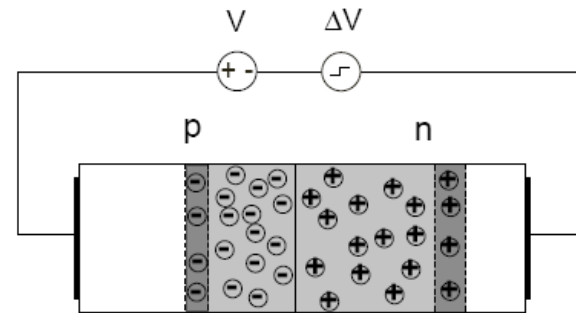
$$C_j = \frac{\epsilon_{si}}{W_{dep}}$$

Disambiguation: here we follow the notation used in most of textbooks, where  $C_j$  stands for capacitance density rather than capacitance. To calculate the final capacitance value one should multiply it by the area:  $S \times C_j$

## Depletion capacitance (1)

- Suppose a small signal,  $\Delta V > 0$  is applied on top of DC bias:

$\Rightarrow$  change of  $\Delta Q_j$  at  $-x_p$   
 $\Rightarrow$  change of  $-\Delta Q_j$  at  $x_n$



## Depletion capacitance (2)

Analogy with a plate capacitor with capacity per unit of area:

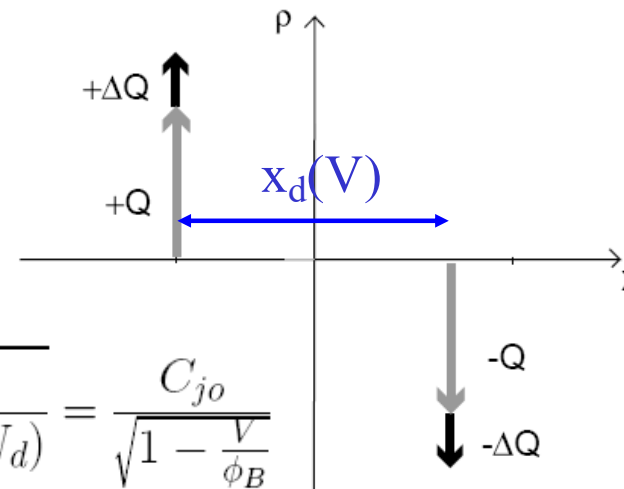
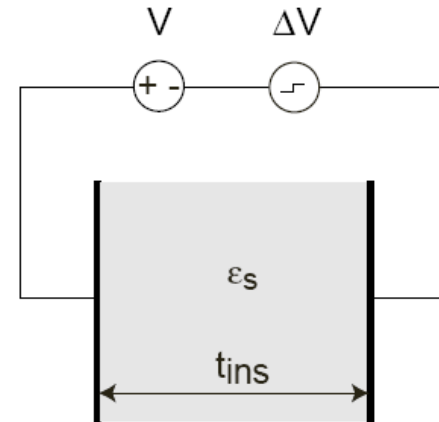
$$C = \frac{\epsilon_s}{t_{ins}}$$

$$x_d(V) = \sqrt{\frac{2\epsilon_s(\phi_B - V)(N_a + N_d)}{qN_aN_d}}$$

Depletion capacitance is:

$$C_j(V) = \frac{\epsilon_s}{x_d(V)} = \sqrt{\frac{q\epsilon_s N_a N_d}{2(\phi_B - V)(N_a + N_d)}} = \frac{C_{j0}}{\sqrt{1 - \frac{V}{\phi_B}}}$$

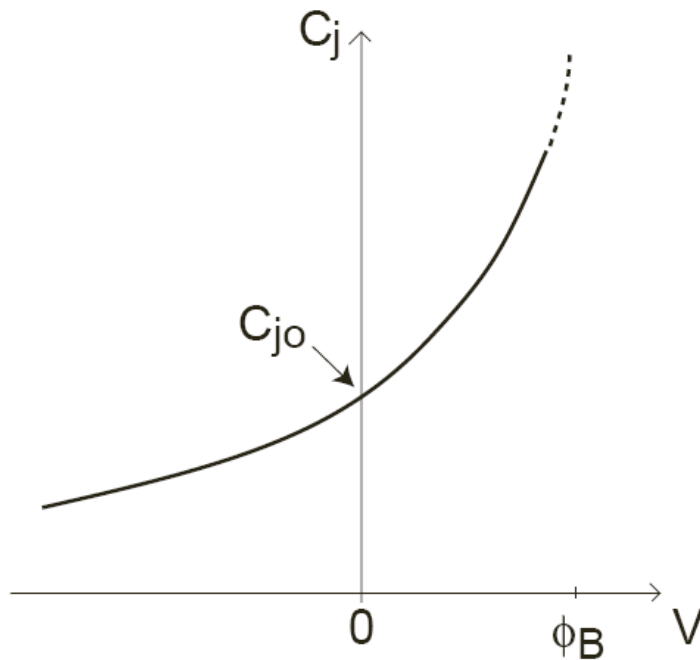
where  $C_{j0}$  is  $C_j$  at  $V=0$





## Depletion capacitance (3)

$$C_j(V) = \frac{\epsilon_s}{x_d(V)} = \sqrt{\frac{q\epsilon_s N_a N_d}{2(\phi_B - V)(N_a + N_d)}} = \frac{C_{jo}}{\sqrt{1 - \frac{V}{\phi_B}}}$$



**$C_j$  depends on:**

- bias,  $V$
- doping,  $N_A$ ,  $N_D$
- in strongly asymmetric junction (i.e. p+n) is dominated by the low doped part:

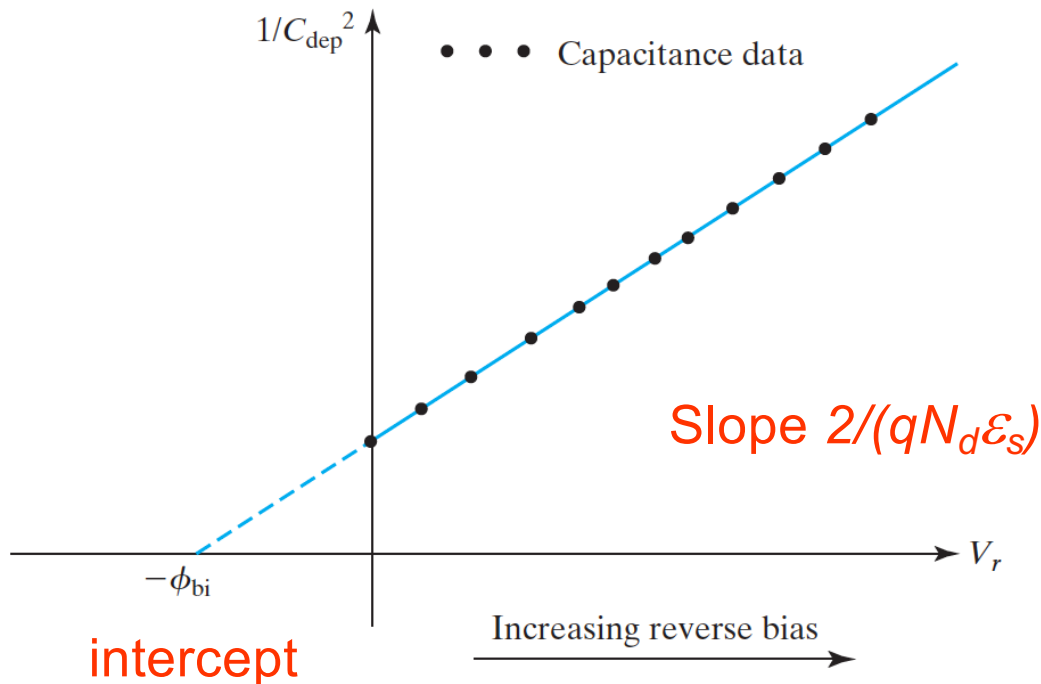
$$C_j(V) \simeq \sqrt{\frac{q\epsilon_s N_d}{2(\phi_B - V)}}$$

## Why capacitance-voltage characteristics of p-n junction are important?

- pn diode= variable capacitor (varicaps, *varactors*):  
     $\Rightarrow$  useful for *voltage-controlled oscillators, other applications where tunable capacitance is useful*
- $C_j$ : important consideration in dynamics of pn diode
- powerful characterization technique:  
*i.e.*  $1/C_j^2$  vs.  $V$  yields  $\phi_B$  and  $N_d$  in asymmetric p<sup>+</sup>-n junctions

## Depletion capacitance (4)

Plot of  $1/C_j^2$  vs.  $V$  known as the [Mott-Schottky plot](#) yields  $\phi_B$  and  $N_d$  in strongly asymmetric p<sup>+</sup>-n junction:

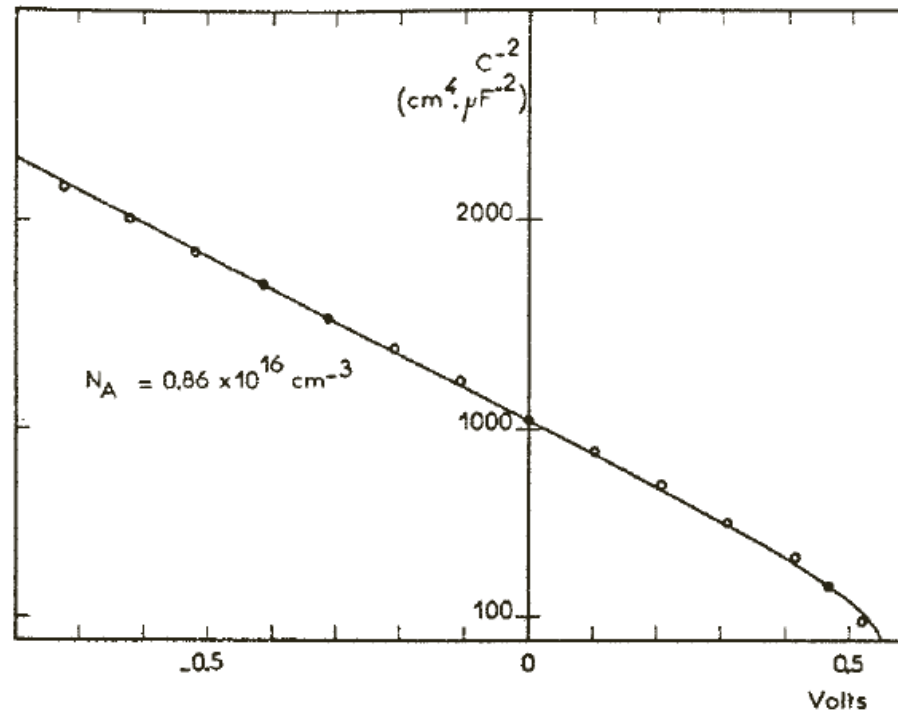


$$\frac{1}{C_j^2} \simeq \frac{2(\phi_B - V)}{q\epsilon_s N_d}$$

- Note that the plotted values represent capacitance density  
If capacitance is plotted, then the slope will be  $2/(qN_d\epsilon_s A^2)$ , where  $A$  is the area

## Depletion capacitance (5), numerical example

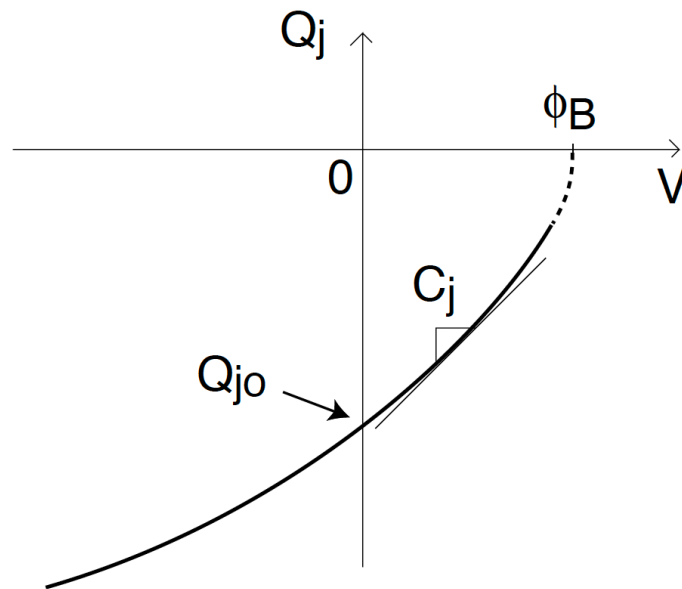
pn+: Calculate  $\phi_B$  and  $N_A$



Experimental data: Fortini et al., IEEE Trans. Electron Dev. ED-29, 1604

## Viewing capacitance of p-n junction in terms of charge

$$Q_j(V) = \sqrt{\frac{2q\epsilon_s N_a N_d (\phi_B - V)}{N_a + N_d}} = Q_{jo} \sqrt{1 - \frac{V}{\phi_B}}$$



$$C_j = \frac{dQ_j}{dV}$$

~~$$C_j = \frac{Q_j}{V}$$~~

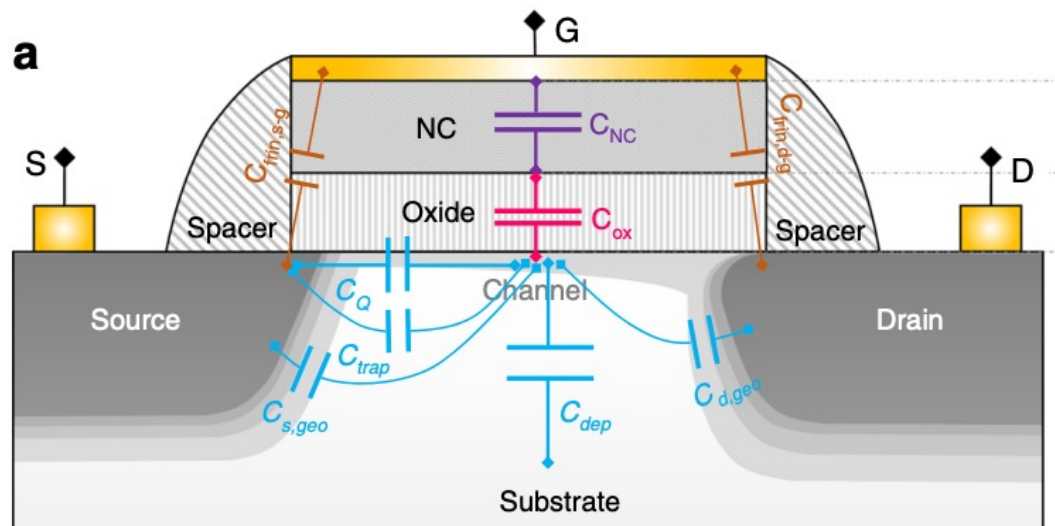
*Wrong!*

## Use of varactors (also known as varicap diodes)

- Microwave Circuits: voltage-controlled oscillators for frequency tuning, phase-locked loops (PLLs) for frequency synthesis.
- Tunable Filters: radio receivers and transmitters to adjust bandpass filters, e.g. to tune antenna matching networks.
- Frequency Modulation (FM) and Phase Modulation Circuits
- TV and Radio Receivers: tuners for channel selection in televisions and radios.

# Capacitance of p-n junction has to be considered in FET design

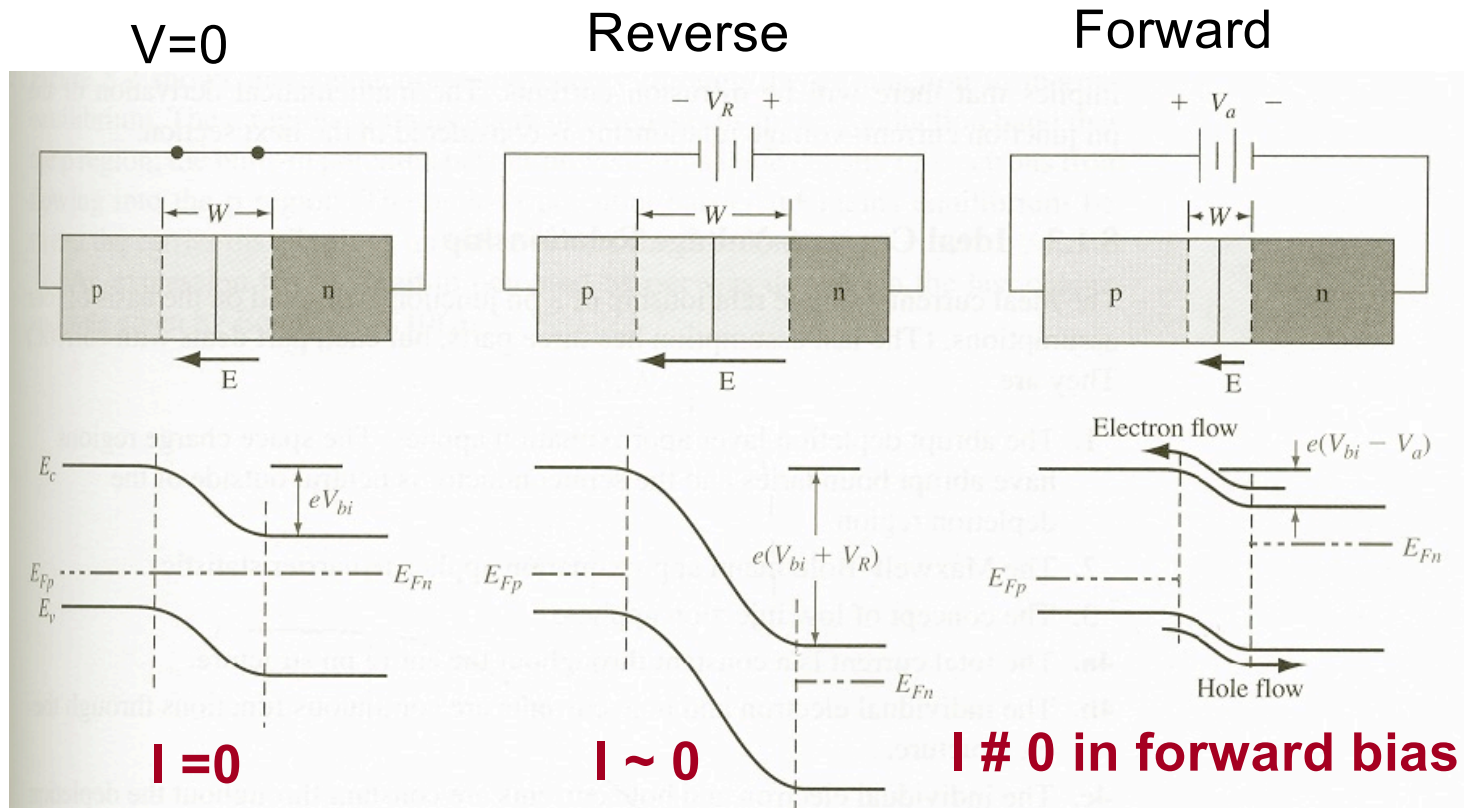
Some of the capacitances within FET are related to the pn junctions



How Junction Capacitance Affects MOSFET Performance:

- Slower Switching Speed: The charge storage in the depletion region of the PN junction introduces parasitic capacitance
- Increased Power Consumption: More capacitance means higher power dissipation (charge/discharge)
- Limits High-Frequency Operation

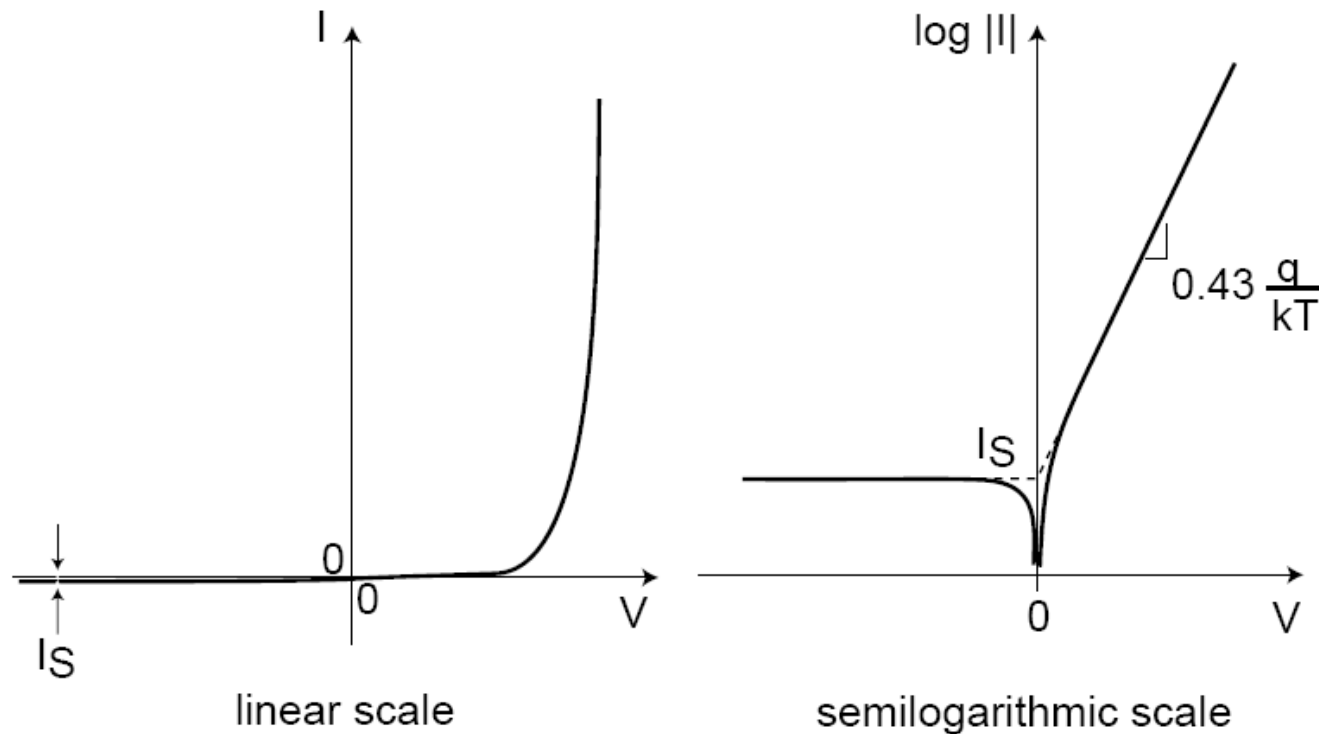
# Transport in pn junctions: Band diagrams

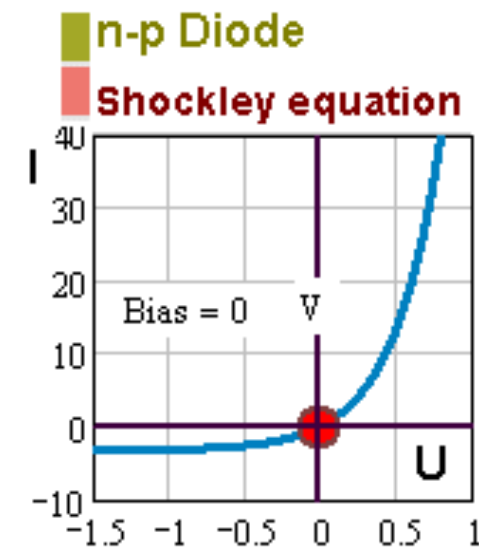
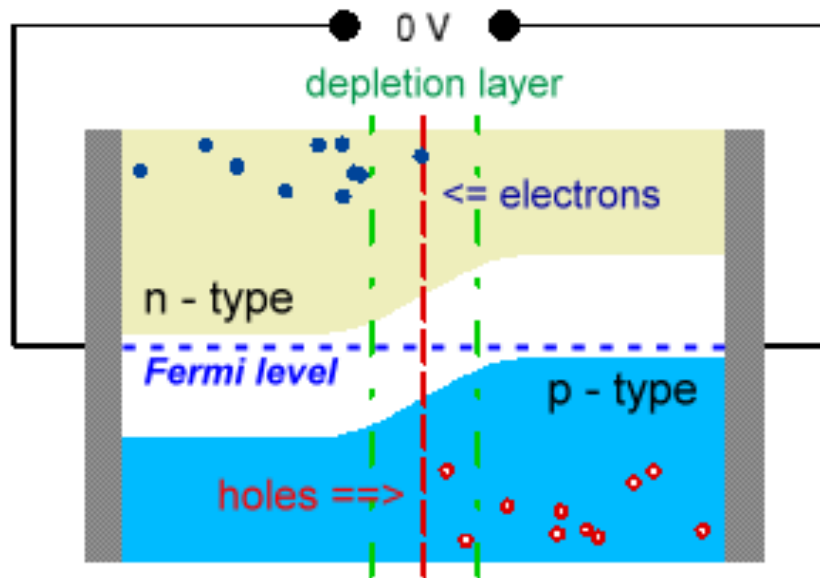




## pn junction = pn diode

Application of voltage to pn junction also results in current (will be studied later → diode): **pn diode!**





In summary, the most important point to remember about the p-n junction diode is its ability to offer very little resistance to current flow in the forward-bias direction but maximum resistance to current flow when reverse biased.

## pn junction under bias: key points

- Voltage applied to pn junction drops across SCR:

⇒ SCR electrostatics modified

- in **forward bias**:  $x_d \downarrow$ ,  $|E| \downarrow$
- in **reverse bias**:  $x_d \uparrow$ ,  $|E| \uparrow$

- Analytical formulation for SCR electrostatics in thermal equilibrium valid under bias if:

$$\phi_B \rightarrow \phi_B - V$$

- As  $V$  changes, SCR charge changes too:

⇒ depletion capacitance,  $C_j$

- pn junction depletion capacitance depends on bias
- in pn junction, current flows for forward bias ( $V > 0$ ), very low current in reverse bias

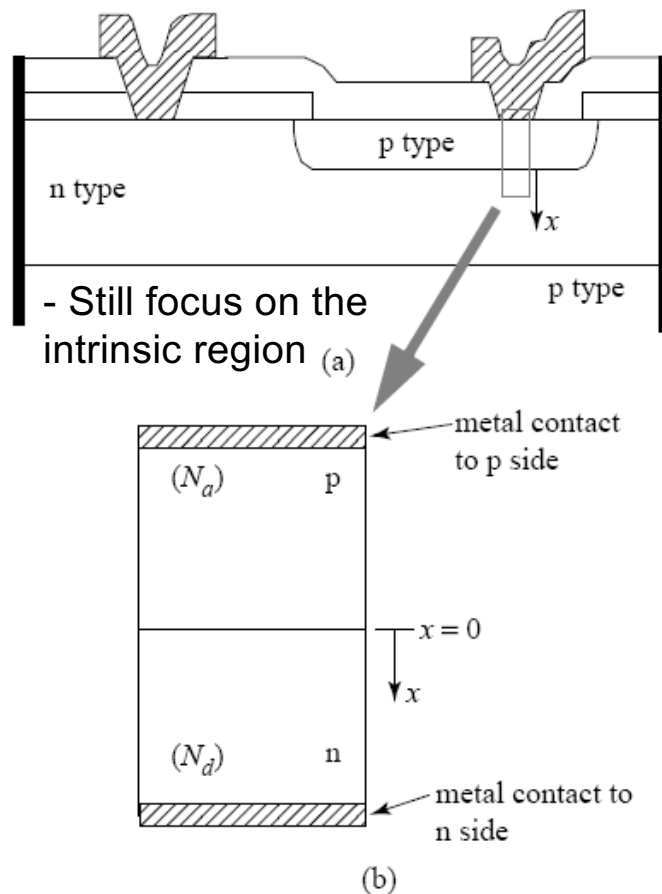
## pn junction under bias: conduction

- pn junction under bias: diode
- I-V characteristics
- Forward conduction
- Breakdown

## Key questions

- Why does the pn junction diode exhibit current rectification?
- Why does the junction current in forward bias increase as:  
 $I \sim \exp(qV/kT)$  ?
- What are the leading dependences of the saturation current (the factor in front of the exponential)?

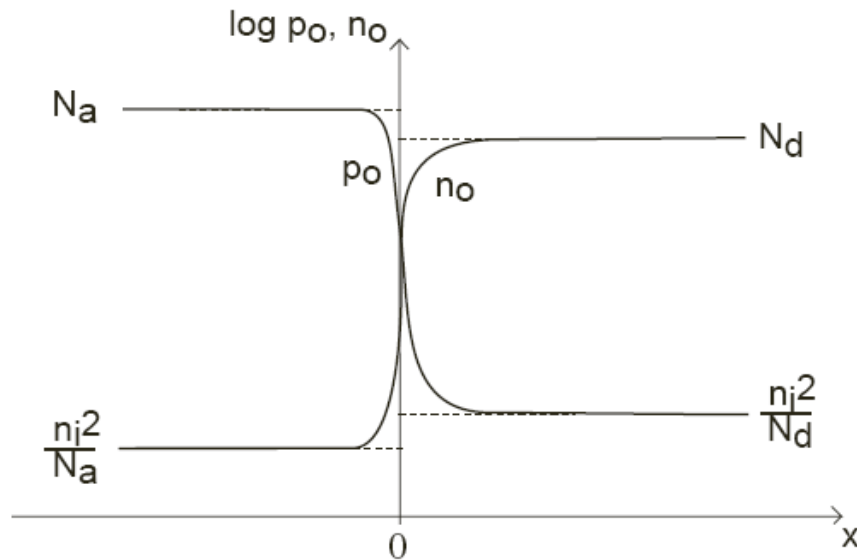
## Pn junction under bias



Upon application of voltage:

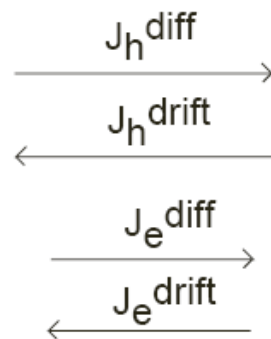
- electrostatics upset: depletion region widens or shrinks
- current flows (with rectifying behavior)
- carrier charge storage

## Carrier profiles @ thermal equilibrium (recall)



Inside SCR in thermal equilibrium: dynamic balance between drift and diffusion for electrons and holes:

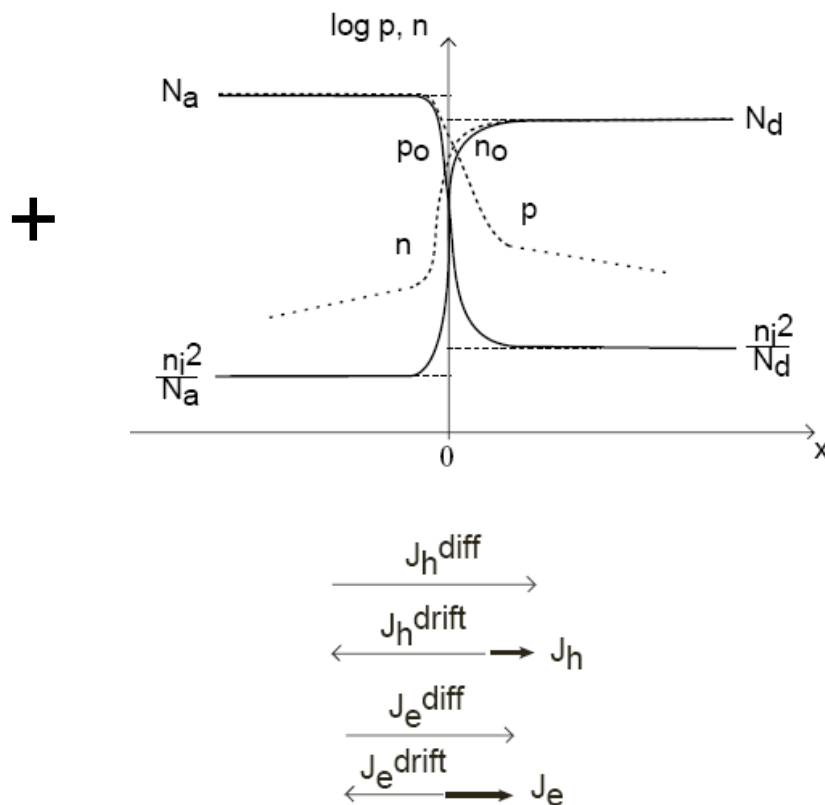
$$|J_{drift}| = |J_{diff}|$$



# Carrier concentrations under bias (1)

Forward bias,  $V > 0$

$$V > 0, \phi_B - V \downarrow \Rightarrow |E_{SCR}| \downarrow \Rightarrow |J_{drift}| \downarrow$$



Current balance in SCR broken:

$$- \quad |J_{drift}| < |J_{diff}|$$

## • Net diffusion current in SCR

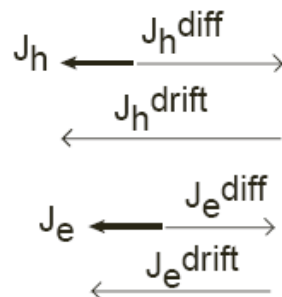
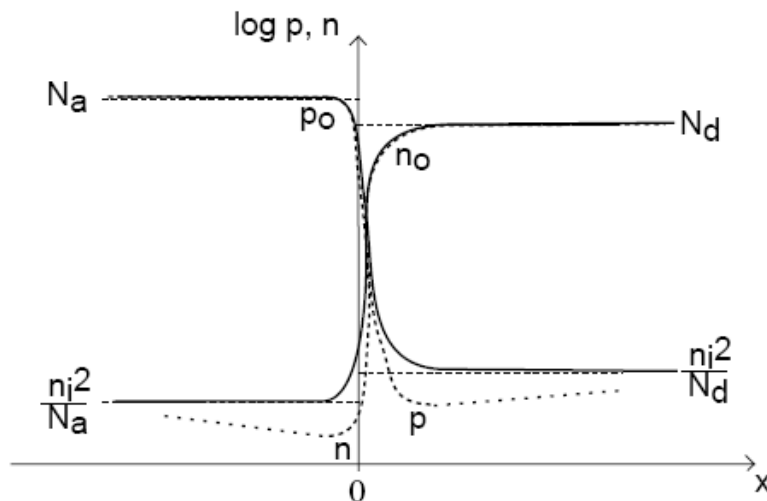
- minority carrier injection into QNR's
- excess minority carrier concentrations in QNR's



## Carrier concentrations under bias (2)

Reverse bias,  $V < 0$

$$V < 0, \phi_B - V \uparrow \Rightarrow |E_{SCR}| \uparrow \Rightarrow |J_{drift}| \uparrow$$



$$+ \quad |J_{drift}| > |J_{diff}|$$

- Net drift current in SCR:
  - minority carrier extraction from QNR's
  - deficit of minority carrier concentrations in QNR's
- Few minority carriers in QNR's: current small

## What happens if minority carrier conc. change from equilibrium in QNR?

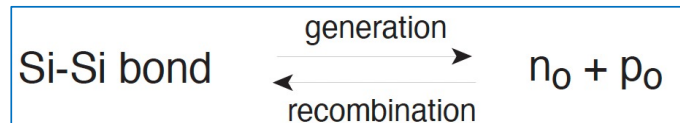
- In thermal equilibrium: rate of break up of Si-Si bonds balanced by rate of formation of bonds



- minority carrier injection:
  - ⇒ - carrier concentration above equilibrium
  - recombination prevails



- minority carrier extraction:
  - ⇒ - carrier concentration below equilibrium
  - generation prevails



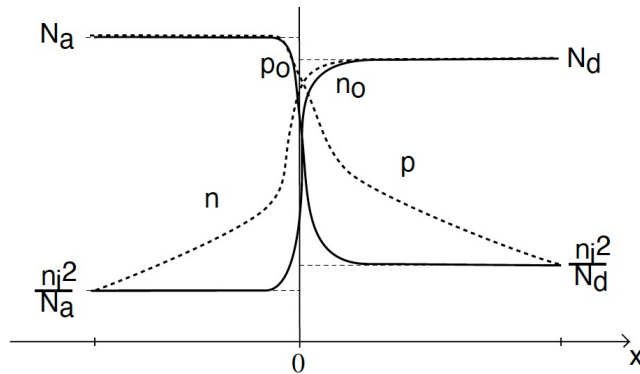
## What happens if minority carrier conc. change from equilibrium in QNR?

- Balance between generation and recombination broken: where does recombination & generation take place?
- In modern devices, **recombination mainly takes place at surfaces**:
  - nearly perfect crystalline periodicity broken at a surface, lots of broken bonds: generation and recombination centers
  - modern devices are very small with high area to volume ratio.
- High generation and recombination activity at surfaces, so that carrier concentrations cannot deviate much from equilibrium values

$$n(s) \simeq n_o, \quad p(s) \simeq p_o$$

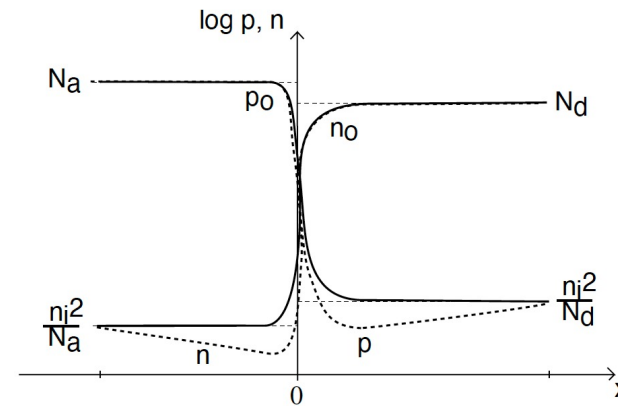
# pn diode current: qualitative view

## Forward bias



Forward bias: injected minority carriers diffuse through QNR  $\Rightarrow$  recombine at semiconductor surface

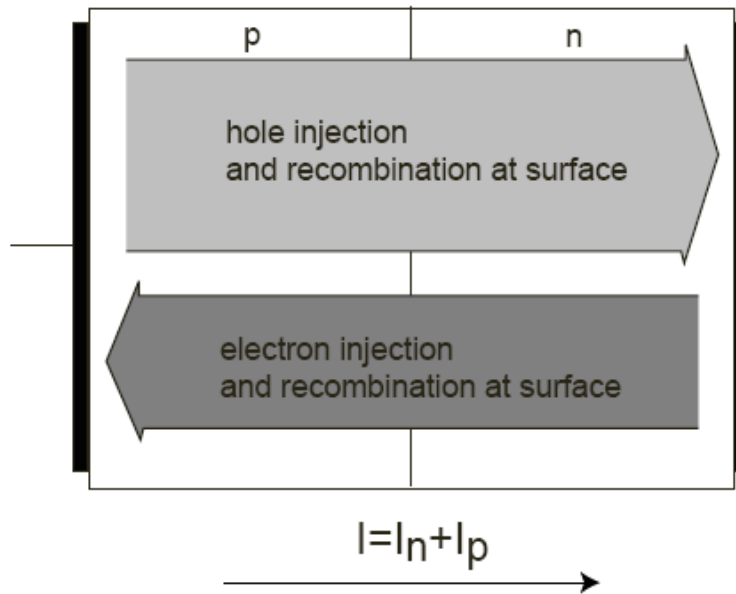
## Reverse bias



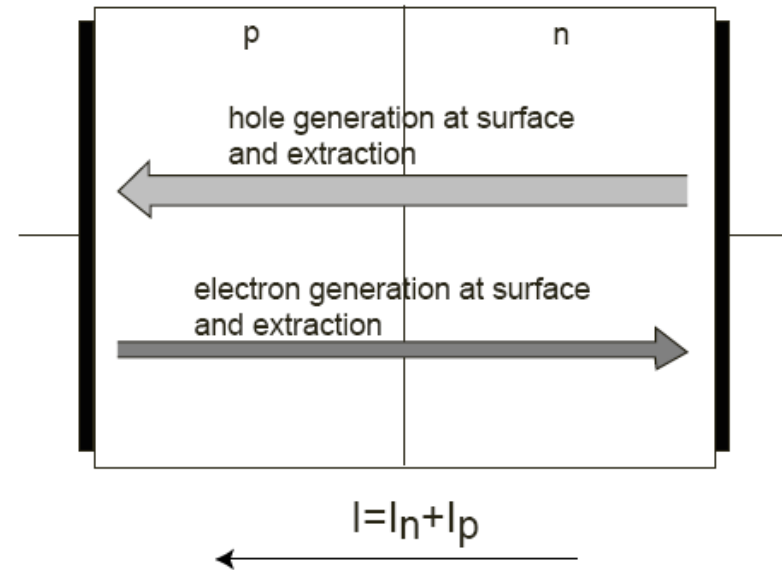
Reverse bias: minority carriers extracted by SCR  
-generated at surface and diffuse through QNR

## pn diode current: qualitative view

Forward bias



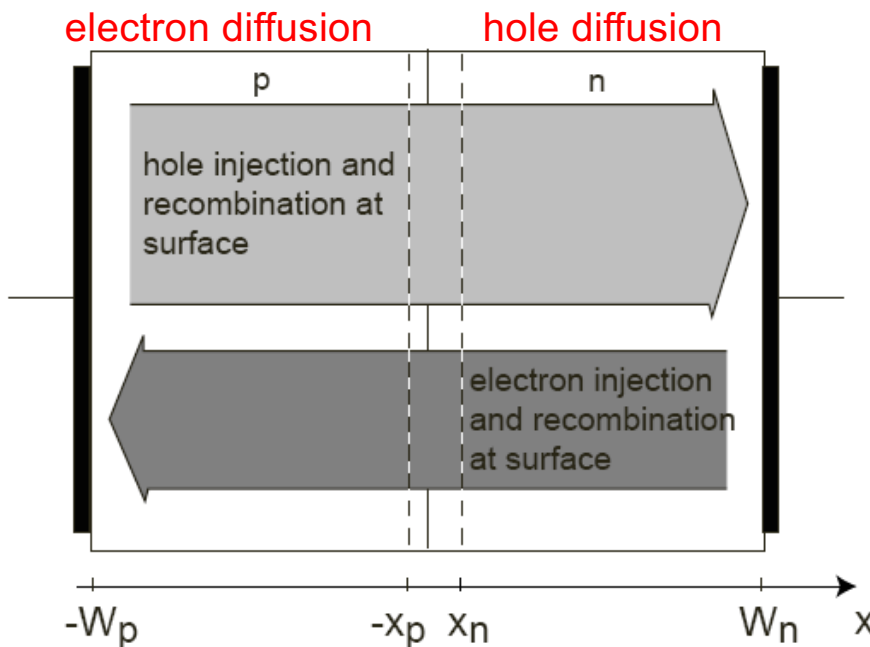
Reverse bias



# pn diode current: magnitude/calculation

What limits the magnitude of the diode current?

- not generation or recombination rate at surfaces
- not injection or extraction rates through SCR
- **diffusion rate through QNR's**



Development of analytical current model, I-V:

1. Calculate concentration of minority carriers at edges of SCR,  $p(x_n)$  and  $n(-x_p)$
2. Calculate minority carrier diffusion current in each QNR,  $I_n$  and  $I_p$
3. Sum electron and hole diffusion currents,  $I = I_n + I_p$

# Diode current calculation (1)

**Step 1:** computation of minority carrier boundary conditions at edges of SCR

## Thermal equilibrium

From L2, slides 14-19:

$$\frac{n_o(x_1)}{n_o(x_2)} = \exp \frac{q[\phi(x_1) - \phi(x_2)]}{kT}$$

$$\frac{p_o(x_1)}{p_o(x_2)} = \exp \frac{-q[\phi(x_1) - \phi(x_2)]}{kT}$$

## Quasi-equilibrium under bias

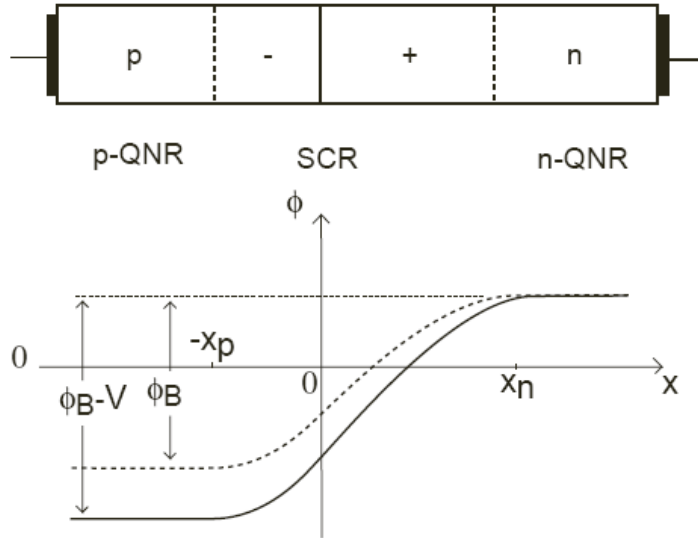
$$|J_{drift}| \neq |J_{diff}|$$

but if difference small with respect to absolute values of current:

$$\frac{n(x_1)}{n(x_2)} \simeq \exp \frac{q[\phi(x_1) - \phi(x_2)]}{kT}$$

$$\frac{p(x_1)}{p(x_2)} \simeq \exp \frac{-q[\phi(x_1) - \phi(x_2)]}{kT}$$

## Diode current calculation (2)



At edges of SCR, then:

$$n(-x_p) \simeq N_d \exp \frac{q(V - \phi_B)}{kT}$$

$$p(x_n) \simeq N_a \exp \frac{q(V - \phi_B)}{kT}$$

$$\frac{n(x_n)}{n(-x_p)} \simeq \exp \frac{q[\phi(x_n) - \phi(-x_p)]}{kT} = \exp \frac{q(\phi_B - V)}{kT}$$

$$\frac{p(x_n)}{p(-x_p)} \simeq \exp \frac{-q[\phi(x_n) - \phi(-x_p)]}{kT} = \exp \frac{-q(\phi_B - V)}{kT}$$

$$p(-x_p) \simeq N_a \quad \text{and} \quad n(x_n) \simeq N_d$$



## Diode current calculation (3)

$$n(-x_p) \simeq N_d \exp \frac{q(V - \phi_B)}{kT}$$

With:  $\phi_B = \frac{kT}{q} \ln \frac{N_d N_a}{n_i^2}$

$$n(-x_p) \simeq \frac{n_i^2}{N_a} \exp \frac{qV}{kT}$$

$$p(x_n) \simeq \frac{n_i^2}{N_d} \exp \frac{qV}{kT}$$

Equilibrium,  $V=0$

$$n(-x_p) = \frac{n_i^2}{N_a} \quad p(x_n) = \frac{n_i^2}{N_d}$$

Forward,  $V>0$

$$n(-x_p) \gg \frac{n_i^2}{N_a} \quad p(x_n) \gg \frac{n_i^2}{N_d}$$

Reverse,  $V<0$

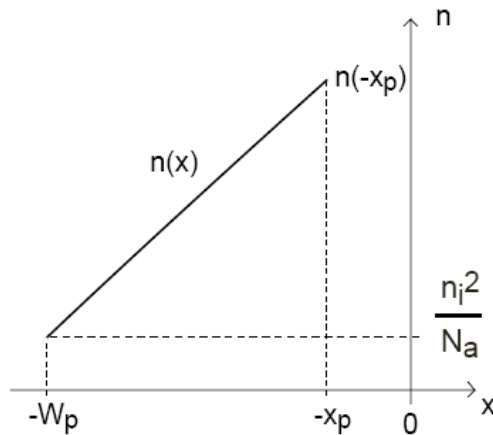
$$n(-x_p) \ll \frac{n_i^2}{N_a} \quad p(x_n) \ll \frac{n_i^2}{N_d}$$

Rectification property of pn diode ( $V>0$  = high current and  $V<0$  = low current) arises from minority carrier boundary conditions at edges of SCR.

## Diode current calculation (4)

### Step 2: Diffusion current in QNR

Diffusion equation (for electrons in p-QNR):  $J_n = qD_n \frac{dn}{dx}$  **Why  $n(x)$  is linear?**



$$n(x = -W_p) = n_o = \frac{n_i^2}{N_a}$$

$$n(-x_p) = \frac{n_i^2}{N_a} \exp \frac{qV}{kT}$$

$$n_p(x) = n_p(-x_p) + \frac{n_p(-x_p) - n_p(-W_p)}{-x_p + W_p}(x + x_p)$$

## Diode current calculation (5)

$$J_n = qD_n \frac{dn}{dx} = qD_n \frac{n_p(-x_p) - n_p(-W_p)}{W_p - x_p}$$

$$= qD_n \frac{\frac{n_i^2}{N_a} \exp \frac{qV}{kT} - \frac{n_i^2}{N_a}}{W_p - x_p}$$

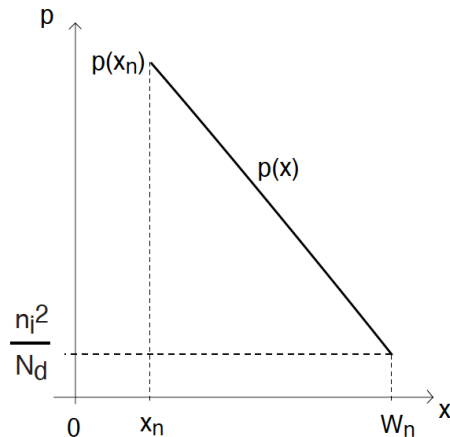
$$J_n = q \frac{n_i^2}{N_a} \frac{D_n}{W_p - x_p} \left( \exp \frac{qV}{kT} - 1 \right)$$

## Diode current calculation (6)

For electrons we just got:

$$J_n = q \frac{n_i^2}{N_a W_p - x_p} \left( \exp \frac{qV}{kT} - 1 \right)$$

For holes - same logic:



$$J_p = q \frac{n_i^2}{N_d W_n - x_n} \left( \exp \frac{qV}{kT} - 1 \right)$$

sum both current components:

$$J = J_n + J_p = q n_i^2 \left( \frac{1}{N_a W_p - x_p} + \frac{1}{N_d W_n - x_n} \right) \left( \exp \frac{qV}{kT} - 1 \right)$$

## Diode current calculation (6)

**Step 3**: sum both current components:

$$J = J_n + J_p = qn_i^2 \left( \frac{1}{N_a} \frac{D_n}{W_p - x_p} + \frac{1}{N_d} \frac{D_p}{W_n - x_n} \right) \left( \exp \frac{qV}{kT} - 1 \right)$$

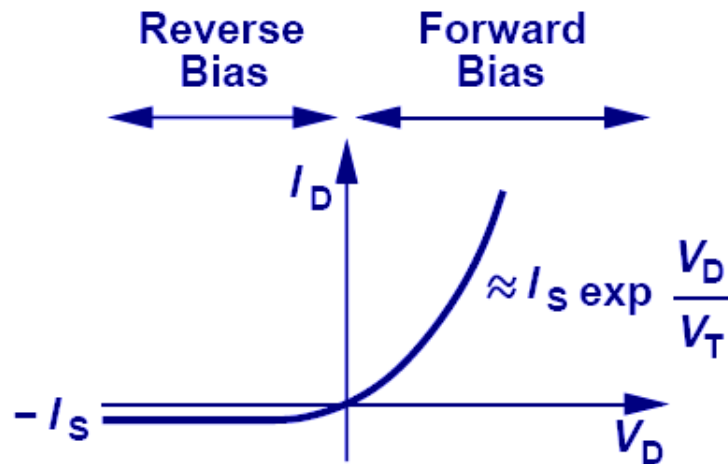
$$I = I_o \left( \exp \frac{qV}{kT} - 1 \right)$$

*$I_o$  is called saturation current [A]*

*This formula is valid for forward and reverse bias*

## Summary I-V characteristics of p-n junction

- Current increases exponentially with applied forward bias voltage, and “saturates” at a relatively small negative current level for reverse bias voltages.



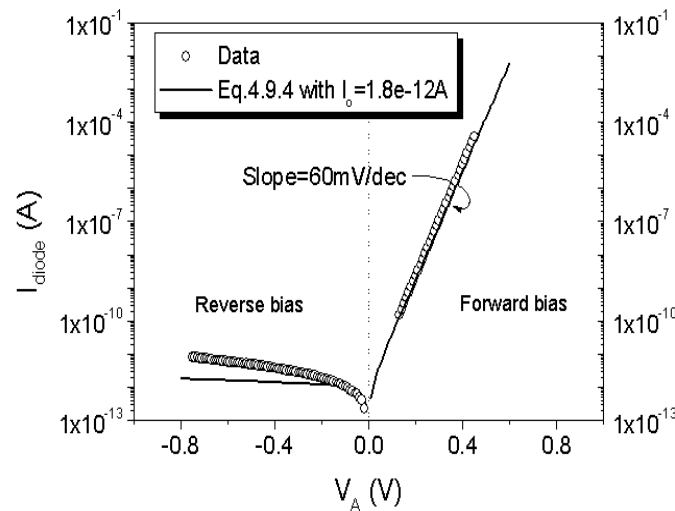
“Ideal diode” equation:

$$I_D = I_S \left( e^{V_D/V_T} - 1 \right)$$
$$I_S = AJ_S = Aqn_i^2 \left( \frac{D_n}{N_A L_n} + \frac{D_p}{N_D L_p} \right)$$

$A$  – area,  $L_n$ ,  $L_p$  – SCR length

# Practical PN Junctions

- Typically, pn junctions in IC devices are formed by counter-doping. The equations provided in class (and in the textbook) can be readily applied to such diodes if
  - $N_A \equiv$  net acceptor doping on p-side  $(N_A - N_D)_{\text{p-side}}$
  - $N_D \equiv$  net donor doping on n-side  $(N_D - N_A)_{\text{n-side}}$



$$I_D = I_S (e^{qV_D/kT} - 1)$$

$$I_S = Aqn_i^2 \left( \frac{D_n}{L_n N_A} + \frac{D_p}{L_p N_D} \right)$$

# Diode Saturation Current $I_S$

$$I_S = Aqn_i^2 \left( \frac{D_n}{L_n N_A} + \frac{D_p}{L_p N_D} \right)$$

- $I_S$  can vary by orders of magnitude, depending on the diode area, semiconductor material, and net dopant concentrations.
  - typical range of values for Si PN diodes:  $10^{-14}$  to  $10^{-17}$  A/ $\mu\text{m}^2$
- In an asymmetrically doped PN junction, the term associated with the more heavily doped side is negligible:

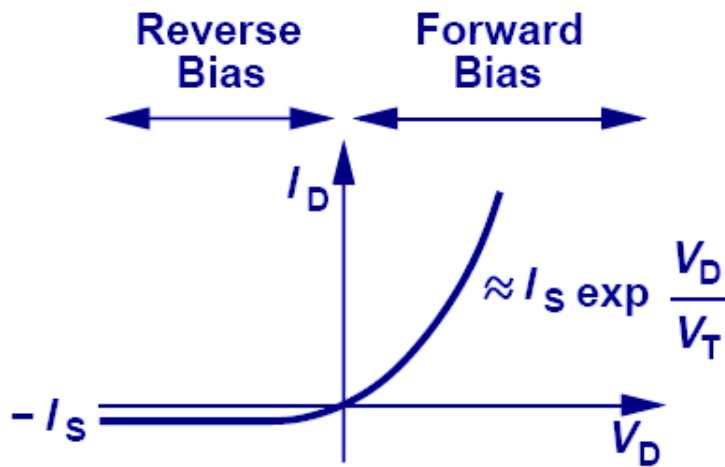
- If the P side is much more heavily doped,  $I_S \cong Aqn_i^2 \left( \frac{D_p}{L_p N_D} \right)$

- If the N side is much more heavily doped,  $I_S \cong Aqn_i^2 \left( \frac{D_n}{L_n N_A} \right)$

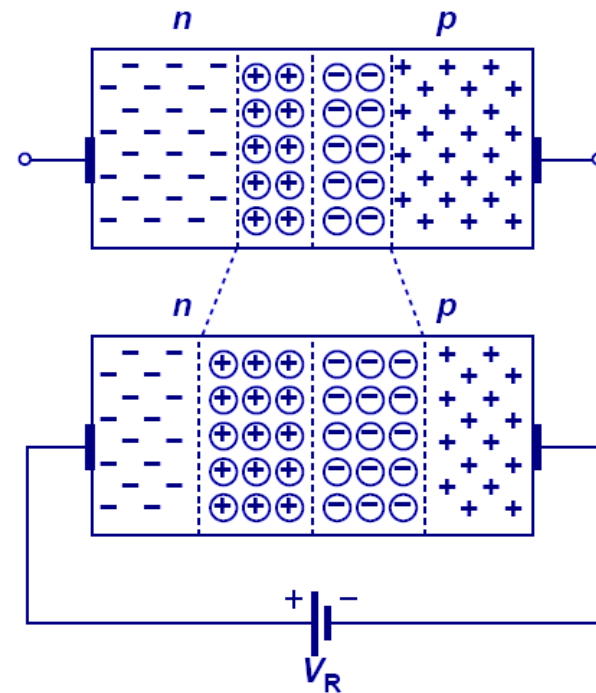


# PN Junction under Reverse Bias

- A reverse bias increases the potential drop across the junction. As a result, the magnitude of the electric field in the depletion region increases and the width of the depletion region widens.

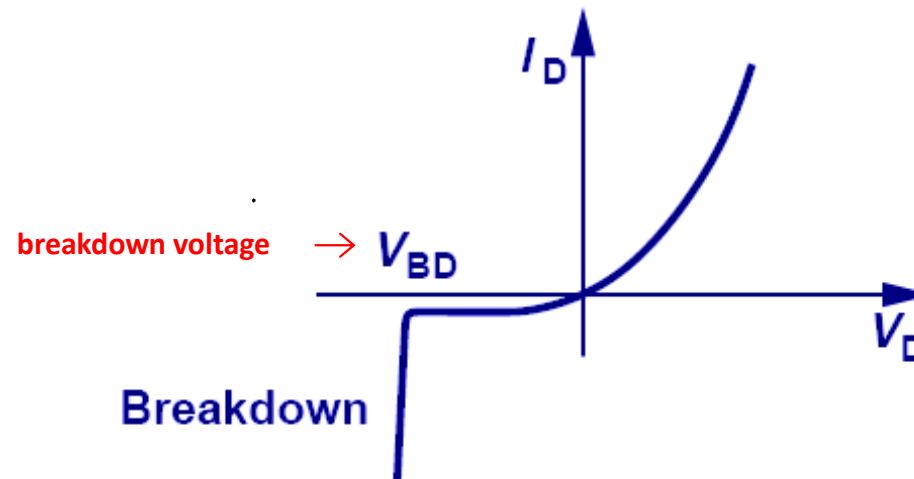


$$W_{dep} = \sqrt{\frac{2\epsilon_{si}}{q} \left( \frac{1}{N_A} + \frac{1}{N_D} \right) (V_0 + V_R)}$$



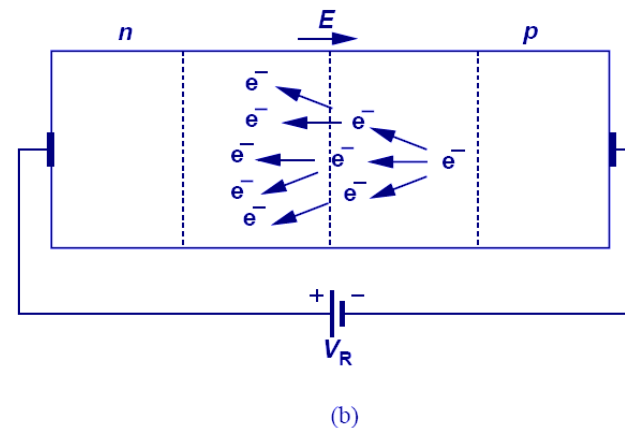
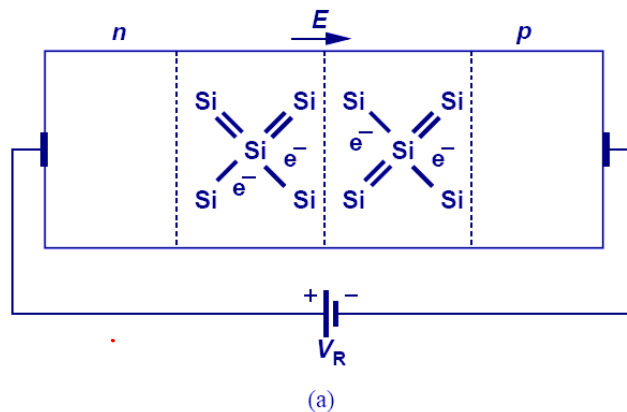
# Reverse Breakdown

- As the reverse bias voltage increases, the electric field in the depletion region increases.
- Eventually, it can become large enough to cause the junction to break down so that a large reverse current flows:



## Reverse Breakdown Mechanisms

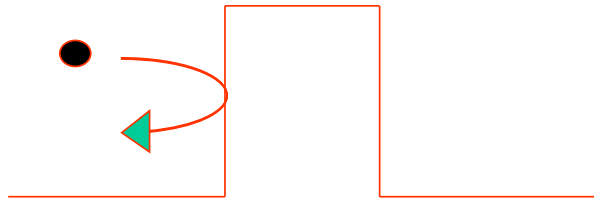
- a) **Zener breakdown** occurs when the electric field is sufficiently high to pull an electron out of a covalent bond (to generate an electron-hole pair).
- b) **Avalanche breakdown** occurs when electrons and holes gain sufficient kinetic energy (due to acceleration by the E-field) in-between scattering events to cause electron-hole pair generation upon colliding with the lattice.



# Tunneling effect and Zener breakdown (1)

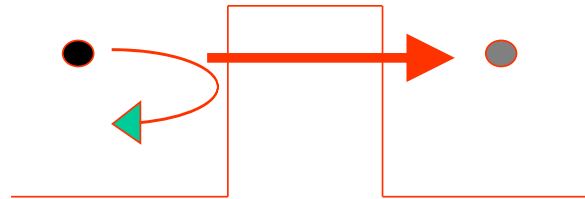
## Phenomenon of tunneling

**Classical case:** there is no chance of the particle being found beyond the barrier.



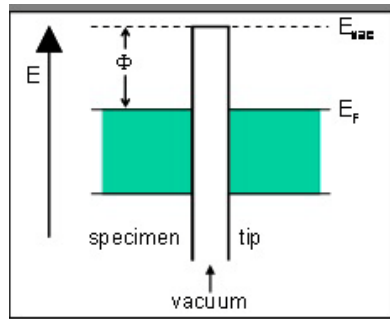
classical barrier – no transmission,  
only reflection

**Quantum mechanics:**  
there is a **probability**  
that the electron can be  
found beyond the barrier.

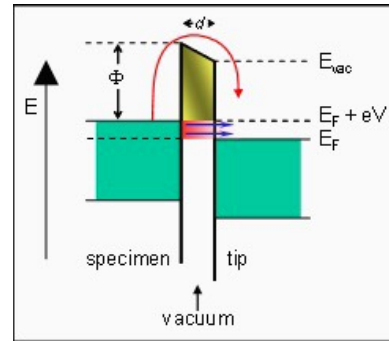


quantum barrier – part transmission,  
part reflection

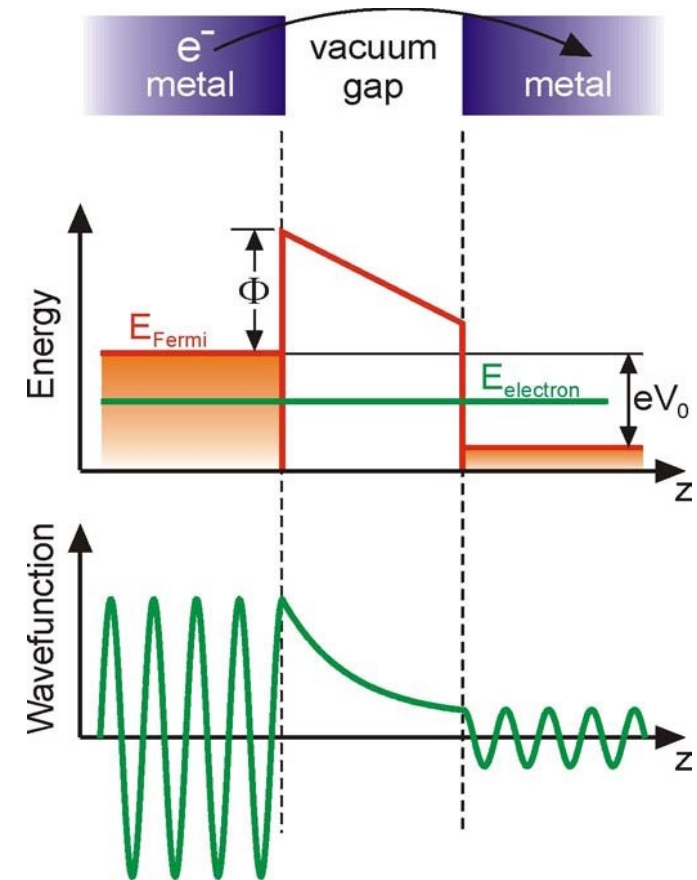
## Tunneling effect and Zener breakdown (2)



When two metal surfaces are brought close to each other, there is only a narrow region of empty space left between them. On either side, the electrons occupy all states up to the Fermi energy. They need to overcome a barrier  $\phi$  to travel from tip to sample or vice versa



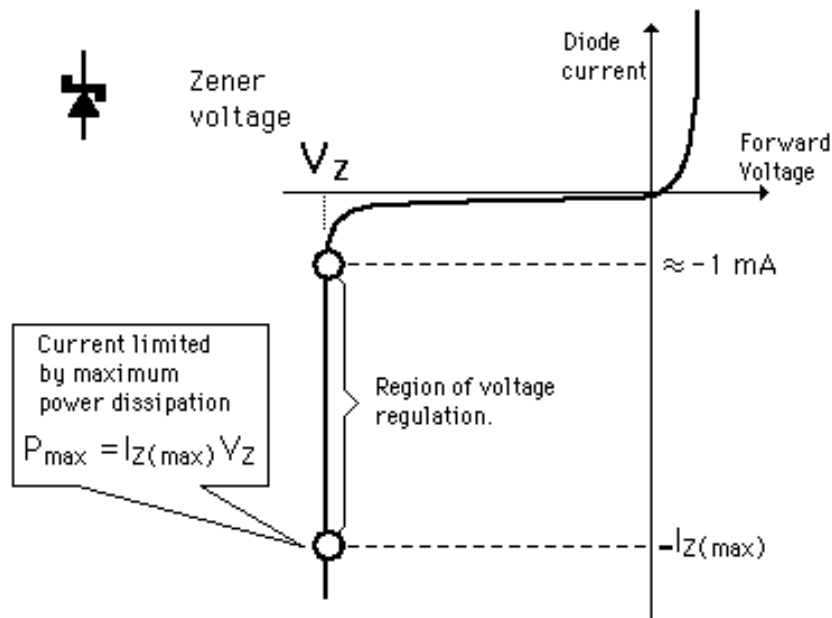
If the distance  $d$  between sample and tip is small enough ( $\text{\AA}$ -range), electrons can 'tunnel' through the vacuum barrier. The direction of tunneling is determined by applied voltage  $V$ , which changes the energy profile as shown above



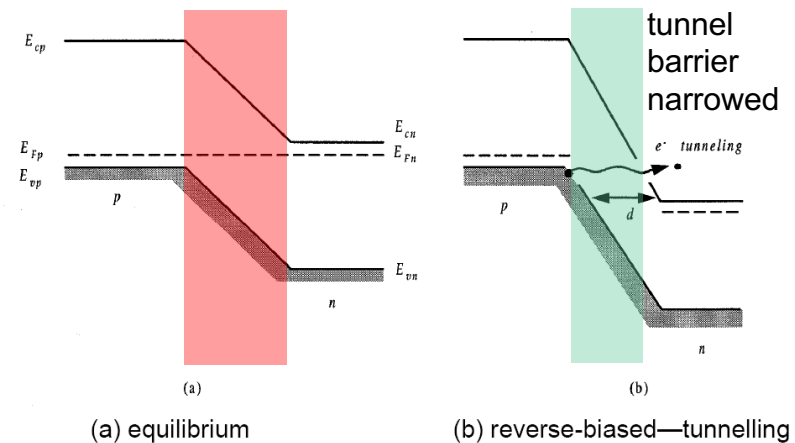
$$I_{tunnel} \propto \exp(-2Kd), \text{ d – barrier thickness}$$

## Tunneling effect and Zener breakdown (3)

- Zener breakdown occurs in heavily doped pn-junctions, which makes the depletion layer extremely thin.
- Carriers cannot accelerate enough to cause impact ionization. With the depletion layer so thin, **quantum mechanical tunneling** occurs causing current to flow.



Energy band representation of the Zener effect

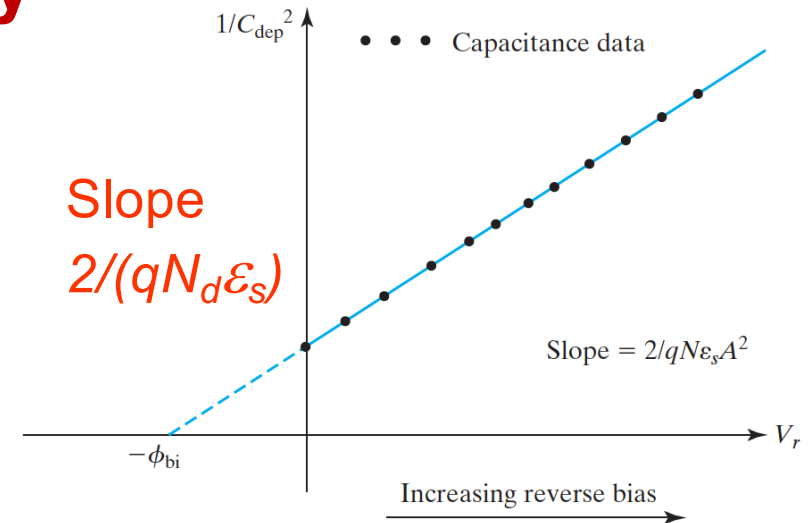


## Summary

- *pn* junction behaves like a capacitor

$$C_j(V) = \frac{\epsilon_s}{x_d(V)} = \sqrt{\frac{q\epsilon_s N_a N_d}{2(\phi_B - V)(N_a + N_d)}} = \frac{C_{j0}}{\sqrt{1 - \frac{V}{\phi_B}}}$$

- pn-junction-based *varactors*
- rectifying properties of pn-junctions
- reverse-biased pn-junction has very low saturation current and sharp reversible breakdown



$$I = I_o \left( \exp \frac{qV}{kT} - 1 \right)$$